



Course Syllabus

Department/Faculty School of Engineering
Graduate Program Materials Engineering and Nanotechnology
Degree <input checked="" type="checkbox"/> Academic Master's <input checked="" type="checkbox"/> Doctorate (PhD) <input type="checkbox"/> Professional Master's
Course Name Microfabrication Techniques
Professor(s) Prof. Cecilia de Carvalho Castro e Silva
Office hours 48
Course Overview <p>Advanced products such as computers, solar cells, cell phones and (biological) sensors are manufactured using microfabrication techniques. Knowledge about micromanufacturing processes is a crucial factor for the advanced manufacturing industry, but also for emerging technologies in start-ups. In this subject, the student will learn to work in a clean room environment, procedures and applications of microfabrication technologies, from the classic processes of lithography, deposition and etching to new technologies for manufacturing devices.</p>
Topics outline <p>i) Practical concepts for working in a clean room environment. ii) Deposition process. Chemical vapor deposition (CVD). Practical example: Growing graphene by CVD. Physical vapor deposition (PVD). Practical example: Deposition of metallic thin films by electron beam (e-beam). iii) Lithography. Describe in detail the two main methods of pattern transfer: electron beam lithography and optical lithography. Practical example: lithography for transferring patterns for metallic contact in graphene devices. iv) Corrosion. The process of wet and dry corrosion will be addressed. The anisotropic corrosion process via reactive ion plasma (RIE). Practical example: corrosion of silicon nitride using RIE. The wet process (in a liquid environment) will be discussed. The main chemical reactions involved in the process will be presented, as well as the isotropic attack. Practical example: use of HF buffer for corrosion of silicon dioxide layer. v) Characterization: Device characterization methods by optical and electrical techniques. vi) Advanced microfabrication technologies. In this topic, the new micromanufacturing processes of devices for optoelectronic, electrical and (bio)sensing applications will be discussed. Focused Ion Beam (FIB) for nanofabrication. Fabrication of microfluidic devices with soft lithography. 3D printing and inkjet printing.</p>
Letter Grade Assignment Grade A (Excellent) - Grade points between 9 and 10 Grade B (Good) - Grade points between 8 and 8.9 Grade C (Satisfactory) - Grade points between 7 and 7.9 Grade D (Unsatisfactory) - Grade points between 0 and 6.9



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Texts, Materials, and supplies

- M. Madou, Fundamentals of Microfabrication, 2nd edition, CRC Press, Boca Raton (2002).
- R. C. Jaeger, Introduction To Microelectronic Fabrication, V 5, 2nd edition, Prentice Hall (2002).